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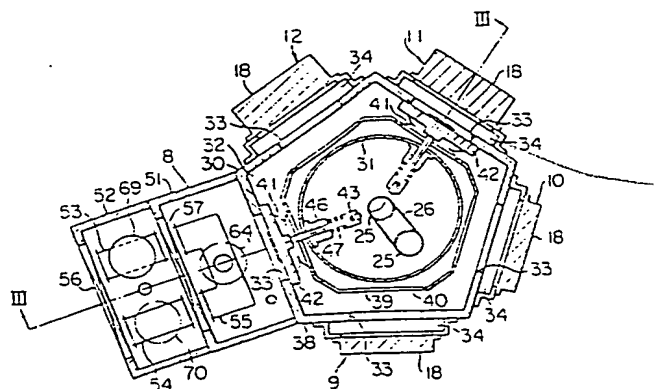
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(54) Continuous sputtering apparatus.

(57) A continuous sputtering apparatus comprising a main vacuum chamber (32), one loading station (8) and a plurality of process stations (9-12) capable of having their pressures controlled separately. The process station includes a sub vacuum chamber (34) capable of being in communication with the main vacuum chamber through an opening (33) and an evacuation port (35). The loading station and the process stations are arranged to be spaced with equal angles. Substrate holders (42) are provided to face the stations and are rotated by said equal angle in a time. The substrate holder opens and closes the opening of the sub vacuum chamber to serve as a gate valve.

FIG. 4



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CONTINUOUS SPUTTERING APPARATUS

1 BACKGROUND OF THE INVENTION

FIELD OF THE INVENTION

The invention relates to a so-called continuous sputtering apparatus capable of producing element thin films of semiconductor devices, devices for communication system and the like by conducting a plurality of processes in a vacuum, and capable of performing these processes continuously.

DESCRIPTION OF THE PRIOR ART

10 Examples of the continuous sputtering apparatus of the prior art including a plurality of process stations are disclosed in Japanese Patent Application Laid-Open No. 100440/1981 (based on U.S. Serial No. 106342), Japanese Patent Application Laid-Open No. 103441/1981 (based on U.S. Serial No. 106179) and Japanese Patent Application Laid-Open No. 103442/1981 (based on U.S. Serial No. 106343). In the continuous sputtering apparatus disclosed in these publications, a pressure of each process station is not independently controlled from other process stations and becomes substantially the same pressure as the other process stations. Since the optimum working pressure of a sputter-deposition process differs from that of a sputter-etching process, the above continuous sputtering apparatus of the prior art has the disadvantages of low process speed

and poor quality of produced films as compared with a case of performing the sputter-deposition process and the sputter-etching process in the optimum working pressures separately. Further, in the prior art, since the process stations are in communication with each other and are evacuated by a single main vacuum pump, impure gases produced in a substrate baking process station and the sputter-etching process station would reach the sputter-deposition process station, resulting in poor quality of produced films.

In addition, a target, which is a source of the produced film, of the sputter-deposition process station is consumed and must be exchanged for new one at regular intervals. In the above continuous sputtering apparatus of the prior art, an atmospheric pressure is to be introduced in a vacuum vessel during the target exchange, and thus it takes a long time to evacuate the vacuum vessel to a clean high vacuum again. As a result, an operation rate of the apparatus is reduced and thus an effective productivity of the apparatus is reduced.

SUMMARY OF THE INVENTION

OBJECT OF THE INVENTION

An object of the invention is to provide a continuous sputtering apparatus capable of controlling a pressure of each process station separately.

Another object of the invention is to provide a continuous sputtering apparatus wherein impure gases

1 produced in any process stations do not reach the other
process stations.

Further another object of the invention is to
provide a continuous sputtering apparatus capable of
5 introducing an atmospheric pressure into only the sputter-
deposition process station during a target of this station
is exchanged for new one.

STATEMENT OF THE INVENTION

To accomplish the above objects, a continuous
10 sputtering apparatus of the invention has the following
features:

at least two process stations each includes a sub
vacuum chamber, gas introduction means connected to the sub
vacuum chamber, an opening making a communication between
15 the sub vacuum chamber and a main vacuum chamber, an
evacuation port making a communication between the sub
vacuum chamber and the main vacuum chamber, valve means
for opening and closing the evacuation port and one of a
sputter-deposition unit and a sputter-etching unit; and
20 substrate transfer means includes drive means for
pushing substrate holders airtightly against the openings
of the process stations and for separating the substrate
holders from the openings, so that the substrate holders
serve as gate valves between the sub vacuum chambers and
25 the main vacuum chamber.

According to the invention, a pressure of each
process station is controlled separately, and thus the

1 sputter-deposition and the sputter-etching are performed in
the optimum working pressures. Further, since the
substrate holders serve as the gate valves between the sub
vacuum chambers and the main vacuum chamber, impure gases
5 produced in any process stations do not reach other process
stations and an atmospheric pressure is introduced into only
the sputter-deposition process station during the target
exchange.

Other features and advantages of the invention will
10 be apparent from the description of the embodiments men-
tioned below and the accompanying drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

Fig. 1 is a front view of a continuous sputtering
apparatus of the prior art;

15 Fig. 2 is a sectional view taken along a line
II-II of Fig. 1;

Fig. 3 is a vertical sectional view of one embodi-
ment of a continuous sputtering apparatus of the invention
and is a sectional view taken along a line III-III of
20 Fig. 4; and

Fig. 4 is a horizontal sectional view taken along
a line IV-IV of Fig. 3.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENT

Before stating embodiments of the invention, one
25 example of the above prior art will be explained in detail
by referring to the accompanying drawings.

1 In Fig. 1, an upward direction corresponds to the
vertically upward direction. In Fig. 2, a leftward direc-
tion is called "front" and a rightward direction is called
"rear" for convenience of explanation.

5 As shown in Figs. 1 and 2, to a vacuum vessel 1
of a thin cylindrical form are connected a gas line 2, a
vacuum valve 3, a variable valve 4 and a vacuum pump 5.
6a is a front wall and 6b is a rear wall.

10 On the front wall 6a of the vacuum vessel 1 are
produced a plurality of openings 7 at the same distances
from the center. At the openings 7 are arranged in order a
loading station 8, the first process station 9, the second
process station 10, the third process station 11 and the
fourth process station 12 as shown in Fig. 1.

15 The loading station 8 is provided with a door 13.
Opening the door 13, catches 23 appear as shown in Fig. 2.
By using the catches 23, a substrate 14 can be mounted on
and separated from a transfer plate 15. The catches 23 for
holding the substrate are disposed at the circumference of
20 a substrate holding hole 22 of the circular transfer plate
15 which is provided adjacent to the front wall 6a.

25 The rear wall 6b of the vacuum vessel 1 is
provided with an air cylinder 20 at a position correspond-
ing to the loading station. The air cylinder 20 can push a
pressure plate 19 toward the transfer plate 15. The central
portion of the rear wall 6b is provided with an air cylinder
21 for driving the transfer plate 15 in the frontward and
rearward direction.

1 The transfer plate 15 is formed with the substrate
holding holes 22 equally spaced from each other and arranged
on a circle having the same radius as a circle on which the
openings 7 are arranged. The transfer plate 15 is rotated
5 by a combination of a motor 24 provided on the front wall
6a, sprocket wheels 25, a chain 26 during not being pressed
by the pressure plate 19. A shaft 27 mounted on an central
axis of the transfer plate 15 and extending frontward and
rearward from the transfer plate 15 is airtightly sealed
10 with the walls 6a and 6b of the vacuum vessel 1.

 There is disposed in the vacuum vessel 1 the
pressure plate 19 movable in the frontward and rearward
direction by an action of the air cylinder 20. A vacuum
preparatory chamber 28 is defined by a cooperation of the
15 door 13, the opening 7 of the loading station 8, the sub-
strate holding hole 22 of the transfer plate 15 and the
pressure plate 19. The pressure plate 19 is formed with
openings 29 at positions corresponding to the first to the
fourth process stations 9-12 of the front wall 6a.

20 Each process station 9-12 is provided with a
sputter-deposition unit or a blind lid 16.

 The continuous sputtering apparatus of the prior
art constructed mentioned above is operated in the following
manner.

25 After evacuating the vacuum chamber 1 to a high
vacuum by the vacuum pump 5, the vacuum valve 3 is opened
and an argon gas is introduced into the vacuum chamber 1
through the gas line 2. A pressure of the vacuum chamber 1

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1 is controlled in any preferred low level by regulating the
variable valve 4. The transfer plate 15 is pressed against
the front wall 6a of the vacuum chamber 1 by the air
cylinder 21 and the pressure plate 19 is pressed against
5 the transfer plate 15 by the air cylinder 20, to form the
vacuum preparatory chamber 28 in the loading station 8.
After the vacuum preparatory chamber 28 is released to the
atmospheric pressure by leak means (not shown), the door 13
is opened and a processed substrate 14 is taken out by
10 carrier means (not shown) and further a new substrate is
mounted on catches 23 in the substrate holding hole 22 of
the transfer plate 15. The door 13 is closed and the vacuum
preparatory chamber 28 is roughly evacuated by rough
evacuation means (not shown). The pressure plate 19, the
15 transfer plate 15 and the front wall 6a are separated from
each other by the air cylinders 20, 21. After the transfer
plate 15 is rotated by an interstation angle by cooperation
of the motor 24, the sprocket wheels 25 and the chain 26,
the front wall 6a, the transfer plate 15 and the pressure
20 plate 19 are brought in intimate contact with each other
again by the air cylinder 20, 21. Next, in the loading
station 8, the above operations are repeated again, and in
the first to the fourth process stations necessary processes
are performed on the substrate 14.

25 Repeating the above operations, the sputtering
processes on the substrate are performed continuously one
by one.

Processes in the process stations may include a

1 baking process wherein the substrate 14 is heated in a
vacuum for removing impure gases adhered to a surface of
the substrate 14, a sputter-etching process wherein argon
ions collide against the surface of the substrate 14 to
5 remove a surface layer of the substrate 14, and a sputter-
deposition process wherein thin films are produced on the
surface of the substrate 14.

In the normal order of the processes, the first
process station 9 performs the baking process or the
10 sputter-etching process, the second process station 10
performs the sputter-etching process or the baking process,
and the third and the fourth process stations 11, 12 perform
the sputter-deposition process.

Next, one embodiment of the invention will be
15 explained by referring to Figs. 3 and 4.

A main vacuum chamber 32 is defined by a pentagonal
vacuum vessel 30 and a lid 31 formed with a cylindrical
recess in the central portion. A wall 38 of the vacuum
vessel 30 is provided with openings 33 which are spaced
20 with equal angles and have the central axis in the same
horizontal plane. There are disposed at the openings a
loading station 8, the first to the fourth process stations
9-12 in order. At the atmosphere side of the loading
station 8 are connected a loading chamber 51 and a take-in-
25 and-out chamber 52. Sub vacuum chambers 34 are formed out-
side the openings 33 of the first to the fourth process
stations 9-12. The sub vacuum chambers 34 and the main
vacuum chamber 32 are able to communicate with each other

1 through evacuation ports 35 and also through the openings
33 as shown in Fig. 3. The evacuation ports 35 are opened
and closed by valves 37 which are driven by air cylinders
36.

5 As shown in Fig. 4, between the vacuum vessel 30
and the lid 31 are provided a drum 39 having a plurality
of flat surfaces 40 substantially parallel to the wall 38
of the vacuum vessel 30. The drum 39 is rotatably supported
at the center of the bottom of the lid 31 and is rotated by
10 cooperation of a motor (not shown), sprocket wheels 25 and a
chain 26.

Each flat surface 40 of the drum 39 is provided
with a substrate holder 42 which is connected to the drum
through a pair of leaf springs 41 and is movable back and
15 forth in maintaining itself substantially parallel to the
flat surface 40. The substrate holder 42 can come into
airtightly contact with the wall 38 of the vacuum vessel 30
when a pusher 43 comes in contact with the substrate holder
42. When a conical cam 45 is lowered by an air cylinder
20 44 (Fig. 3) mounted on the center of the recess of the lid
31, the pushers 43 are moved outward and guided in guide
members 46 to push the substrate holders 42 against the wall
38 at the all stations at the same time. When the conical
cam 45 ascends, the pushers 43 are withdrawn by compression
25 coil springs 47 so that outer ends of the pushers 43 are
withdrawn to an outer peripheral surface of the recess of
the lid 31, and further the substrate holders 43 are
separated from the wall 38 and approach the drum 39 by

1 actions of the leaf springs 41 (Fig. 4).

In Fig. 4, it should be understood that the pushers 43, the guide members 46, the substrate holders 42 and the leaf springs 47 are omitted from the drawings in the first, 5 the second and the fourth process stations 9, 10, 12.

As shown in Fig. 3, at least two sub vacuum chambers 34 each has a process unit 18, a gas line 2, a vacuum valve 3 and a variable valve 4. These components are same or like ones as in the prior art apparatus shown in Fig. 2.

10 The main vacuum chamber 32 is connected to a vacuum pump 5 through a main valve 71 and a pipe 48 and evacuated to a high vacuum.

At the atmosphere side of the loading station 8 is provided the loading chamber 51, and further at the 15 atmosphere side of the loading chamber 51 is provided the take-in-and-out chamber 52. Two sets of carrier means 53, 54 are provided in the take-in-and-out chamber 52 and one set of carrier means 55 is provided in the loading chamber 51.

20 Two gate valves 56 and 57 are provided on both sides of the take-in-and-out chamber 52. When the gate valve 56 is opened, the substrate 14 is taken in into the take-in-and-out chamber 51 by carrier means (not shown) provided in the atmosphere. When the gate valve 56 is 25 closed and the gate valve 57 is opened, the substrate 14 is transferred from the chamber 52 to the chamber 51 or from the chamber 51 to the chamber 52 by the carrier means 53, 54, 55.

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1 The take-in-and-out chamber 52 is, as shown in Fig.
3, connected to an auxiliary vacuum pump 60 through a
vacuum pipe 58 and a vacuum valve 59 and is connected to a
source of a leak gas (not shown) through a leak line 61 and
5 a leak valve 62.

 The loading chamber 51 is connected to the vacuum
pump 5 through a bypass pipe 63, a valve 72 and the pipe 48.

 When the substrate 14 is in the loading position
64 (Fig. 4) in the loading chamber 51, the substrate 14 is
10 lifted by an elevator 65 shown in Fig. 3 and held on an
arm 66 (Fig. 3). A holding mechanism is omitted from the
drawings. The arm 66 is rotated around an axis 67 (shown as
a cross of lines), and the substrate 14 is transferred to
the substrate holder 42.

15 The elevator 65 is driven as by an air cylinder
68 and the arm 66 is driven by a motor (not shown).

 Rough evacuation pipes 73 and 74 are connected
between the vacuum pump 5 and the auxiliary vacuum pump 60
and between the sub vacuum chambers 34 and the auxiliary
20 vacuum pump 60 for roughly evacuating the non-operated
vacuum pump 5 and the sub vacuum chamber 34. Valves 75 and
76 are provided midway of the rough evacuation pipes 73 and
74.

 A cryo-pump is used for the vacuum pump 5 and
25 an oil rotary pump is used for the auxiliary vacuum pump 60.
The substrate holder 42 is designed for 4-inches wafers, but
can be modified for 5-inches or 6-inches wafers.

 Next, an operation of the continuous sputtering

1 apparatus constructed above will be described.

5 The substrate holder 42 is maintained to be pressed against the wall 38 of the vacuum vessel 30 in each station by holding the conical cam 45 in the lower position by the air cylinder 44. The vacuum pump 5 is operated in the condition that the valve 37 is opened by the air cylinder 36, and the argon gas is introduced into the sub vacuum chamber 34 of the sputter-deposition and the sputter-etching stations through the gas line 2 by regulating the vacuum valve 3 and the variable valve 4, to make pressures of the sub vacuum chambers 34 and the main vacuum chamber 32 predetermined low levels. The pressure of the sub vacuum chamber 34 is controlled by regulating a degree of opening of the variable valve 4 and by modifying a diameter of the evacuation port 35.

The gate valves 56 and 57 and the vacuum valve 59 are closed, and the leak valve 62 is opened to introduce a leak gas (dry nitrogen gas) into the take-in-and-out chamber 52 to the atmospheric pressure.

1 The loading chamber 51 is evacuated to a pressure of the order of 10^{-7} Torr by using the bypass pipe 63. The elevator 65 is in the lowest position in the loading chamber 51.

5 The operation cycle starts from the above conditions.

The gate valve 56 of the take-in-and-out chamber 52 is opened. The substrate 14 is carried to the take-in position 69 by cooperation of the carrier means provided in

1 the atmosphere (not shown) and the carrier means 53. And
then the gate valve 56 is closed.

The auxiliary vacuum pump 60 is operated. The
vacuum valve 59 is opened to evacuate the take-in-and-out
5 chamber 52 to 0.1 Torr for example, and thereafter the gate
valve 57 is opened. The substrate 14 is transferred to the
loading position 64 by cooperation of the carrier means 53
and 55. And then the substrate 14 is mounted on the
substrate holder 42 by cooperation of the elevator 65 and
10 the arm 66.

The conical cam 45 is raised. The pushers 43
are moved inward by the compression coil springs 47 and
the substrate holders 42 are also moved inward by the leaf
springs 41. The drum 39 is rotated by one interstation
15 angle by cooperation of the motor, the sprocket wheels
25 and the chain 26. The substrate holders 42 are pressed
against the wall 38 of the vacuum vessel 30 again by
cooperation of the air cylinder 44, the conical cam 45 and
the pushers 43. The processed substrate 14 mounted on the
20 substrate holder 42 is transferred to the carrier means 55
by cooperation of the arm 66 and the elevator 65 in the
loading station 8. After opening the gate valve 57, the
substrate 14 is carried to the take-out position 70 in the
take-in-and-out chamber 52 by cooperation of the carrier
25 means 53 and 54. And then a new substrate 14 is carried
from the take-in position 69 to the loading position 64 and
the gate valve 57 is closed.

As described above, after releasing the take-

1 in-and-out chamber 52 to the atmosphere and opening the gate
valve 56, there are conducted at the same time taking in
the new substrate 14 and taking out the processed substrate
14 from the take-out position 70.

5 During the taking-in and taking-out processes in
the loading station 8, the substrates 14 are subjected to
the predetermined processes in the first to the fourth
process stations.

In the first process station is performed the
10 wafer baking process for removing impure gases adhered to
the wafer surface. In the second process station is
performed the sputter-etching process for removing oxide
layers of the wafer surface before the sputter-deposition.
In the third process station is performed the sputter-
15 deposition process for forming thin films on the wafer.
In the fourth process station can be performed another
sputter-deposition process using another target material.
Stating concretely, the target material of the third
process station is M_oS_{i2} for gate electrodes of LSI memories
20 and the target material of the fourth process station is
aluminum alloy for wiring films. It is noted, however,
that the above two sputter-deposition processes are not
continuously performed on the same wafer.

In selecting the above processes, the process
25 units 18 of the respective process stations are a wafer
baking unit in the first process station, a sputter-etching
unit in the second process station, sputter-deposition units
in the third and the fourth process stations.

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1 Argon gas pressures of the respective chambers of
the above embodiment is as follows:

	main vacuum chamber:	1 mTorr
5	sub vacuum chamber of the first process station:	1 mTorr
	sub vacuum chamber of the second process station:	8 mTorr
	sub vacuum chambers of the third and fourth process stations:	2 mTorr

10 Repeating the above operations, a number of the
substrates 14 are separately and continuously subjected to
the sputtering processes.

The target of the sputter-deposition process is
consumed. The target exchange is performed in the following
15 manner.

The five substrate holders 42 are pressed against
the wall 38 by cooperating the air cylinder 44, the conical
cam 45 and the pushers 43. There is closed the valve 37 of
the station at which the target should be exchanged for new
20 one by the action of the air cylinder 36 thereof, to
airtightly seal the pertinent sub vacuum chamber 34 with
respect to the main vacuum chamber 32. The sub vacuum
chamber 34 is released to the atmospheric pressure by leak
means (not shown). And then the sputtering electrode of
25 the process unit 18 of the station is taken out and the
target is exchanged for new one. After the target exchange,
the sputtering electrode is assembled and the sub vacuum
chamber 34 is roughly evacuated by the rough evacuation
means 74 and 76. Next, the substrate holders 42 are

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1 withdrawn to evacuate the sub vacuum chamber 34 to a high
vacuum.

According to the invention, as seen from the above
description, it is sufficient for the target exchange to
5 introduce the atmospheric pressure into only the pertinent
sub vacuum chamber 34 of the station at which the target
should be exchanged for new one with the main vacuum
chamber 32 being under evacuation in a high vacuum.

While the above embodiment has five stations
10 including one loading stations and four process stations,
any numbers of the stations may be provided in performing
the invention.

The above embodiment has the loading chamber 51
and the take-in-and-out chamber 52 in the loading station
15 8. The loading chamber 51, however, may be omitted and thus
the take-in-and-out chamber 52 may be directly connected to
the main vacuum chamber 32. In this case, the elevator 65
and the loading arm 66 are to be provided in the take-in-
and-out chamber 52. This modification has a similar effect
20 as the above embodiment.

The above embodiment of the invention has one set
of the main evacuation system. And in the embodiment the
pressure of each sub vacuum chamber is separately controlled
by providing each process station with the sub vacuum
25 chamber. As a result, the optimum pressure can be set in
each process to improve the process speed and the film
quality. Further, the impure gases produced in the baking
process station and the sputter-etching process station are

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1 discharged from the evacuation ports into the main vacuum
chamber and finally to the vacuum pump. It is noted that
the impure gases discharged into the main vacuum chamber
hardly enter other sub vacuum chambers through the evacua-
5 tion ports thereof. This entrance probability of the impure
gases into the other sub vacuum chambers would be
practically negligible. Namely, it would be neglected that
the impure gases affect the sputter-deposition process.

The embodiment includes the substrate holders 42
10 rotatable around the vertical axis and thus the substrates
14 rotate in the horizontal plane. Accordingly, there is
avoided adhesion of dust to the substrate, the dust coming
down from upward, as compared with the prior art including
the substrate holder rotatable in the vertical plane.

15 According to the invention, since the mechanism
in the main vacuum chamber does not touch the atmosphere,
the substrate holder, which is subjected to a high tempera-
ture in the baking process station, does not cooled by the
atmosphere. As a result, there is avoided scaling off the
20 deposited film on the substrate holder, the scaling off
being caused by repeating heating and cooling. Since the
mechanism in the main vacuum chamber does not touch the
atmosphere, there is of course reduced the entrance of gases
involved in the atmosphere into the main vacuum chamber,
25 these gases being undesirable for the sputter-deposition
process.

C l a i m s

1. A continuous sputtering apparatus comprising:
a vacuum vessel (30) forming a main vacuum chamber (32);
evacuation means (5) connected to the vacuum vessel;
a plurality of stations consisting of one loading station (8) and a plurality of process stations (9-12) and arranged to be spaced with equal angles on a wall (38) of the vacuum vessel; and
substrate transfer means (39) including substrate holders (42), which are same in number as the stations and face the stations, and enabling the substrate holders to rotate by said equal angle in a time in the main vacuum chamber,
characterized in that
at least two said process stations (9-12) each includes a sub vacuum chamber (34), gas introduction means (2-4) connected to the sub vacuum chamber, an opening (33) making a communication between the sub vacuum chamber and the main vacuum chamber (32), an evacuation port (35) making a communication between the sub vacuum chamber and the main vacuum chamber, valve means (37) for opening and closing the evacuation port and one of a sputter-deposition unit (18) and a sputter-etching unit (18); and
said substrate transfer means (39) includes drive means (43-47) for pushing the substrate holders (42) airtightly against the openings (33) of the process stations

(9-12) and for separating the substrate holders from the openings, so that the substrate holders serve as gate valves between the sub vacuum chambers and the main vacuum chamber.

2. A continuous sputtering apparatus as claimed in claim 1, wherein said substrate transfer means (39) enables the substrate holders (42) to rotate around a vertical axis.

3. A continuous sputtering apparatus as claimed in claim 1, wherein said loading station (8) includes a take-in-and-out chamber (52) capable of being evacuated, substrate carrier means (53, 54) provided in the take-in-and-out chamber and loading means (51) for transferring the substrate (14) between the substrate carrier means and the substrate holder (42).

4. A continuous sputtering apparatus as claimed in claim 3, wherein said loading means (51) includes a loading chamber (51) provided between the vacuum vessel (30) and the take-in-and-out chamber (52).

5. A continuous sputtering apparatus as claimed in claim 4, wherein said evacuation means (5) and said loading chamber (51) are connected to each other through a bypass pipe (63).

6. A continuous sputtering apparatus as claimed in claim 1, comprising four process stations (9-12) each including the sub vacuum chamber (34), the process stations having, respectively in order, a substrate baking unit (18), a sputter-etching unit (18), a sputter-deposition unit (18)

and a sputter-deposition unit (18).

7. A continuous sputtering apparatus as claimed in claim 6, wherein said vacuum vessel (30) has a horizontal cross section of pentagonal shape.

8. A continuous sputtering apparatus as claimed in claim 1, wherein said drive means (43-47) includes a conical cam (45) movable upward and downward on a central axis of rotation of the substrate holders (42), pushers (43) movable horizontally by being pressed against the conical cam (45) by compression coil springs (47) to push the substrate holders (42) outward and leaf springs (41) pulling the substrate holders inward.

FIG. 1 PRIOR ART

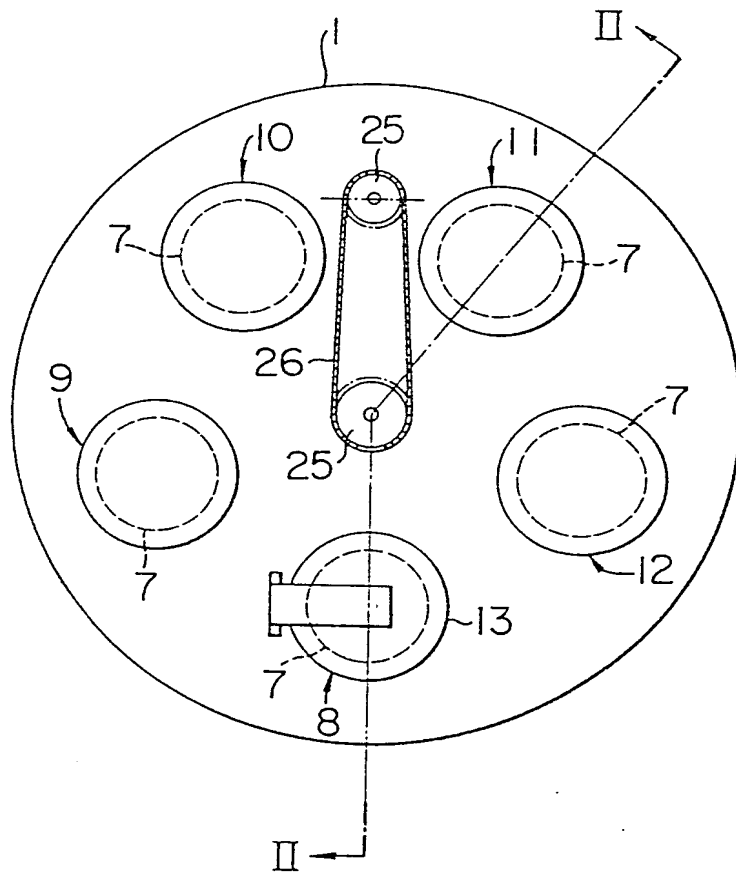
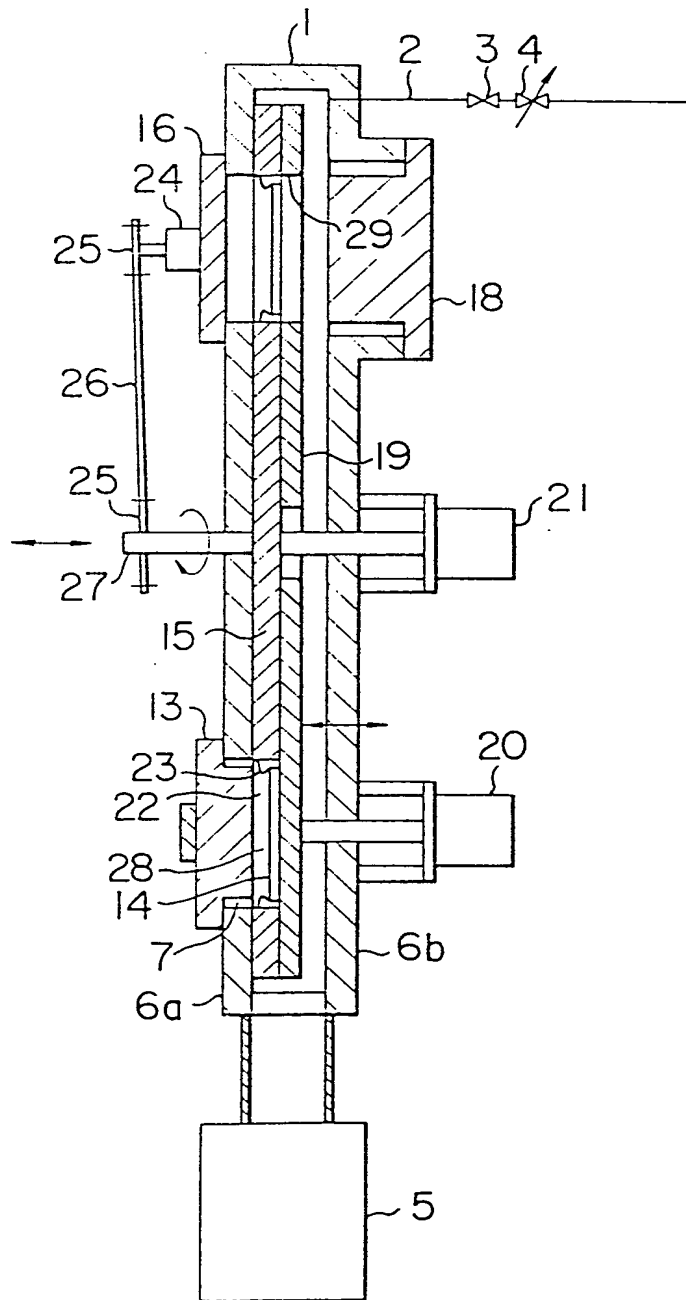


FIG. 2 PRIOR ART



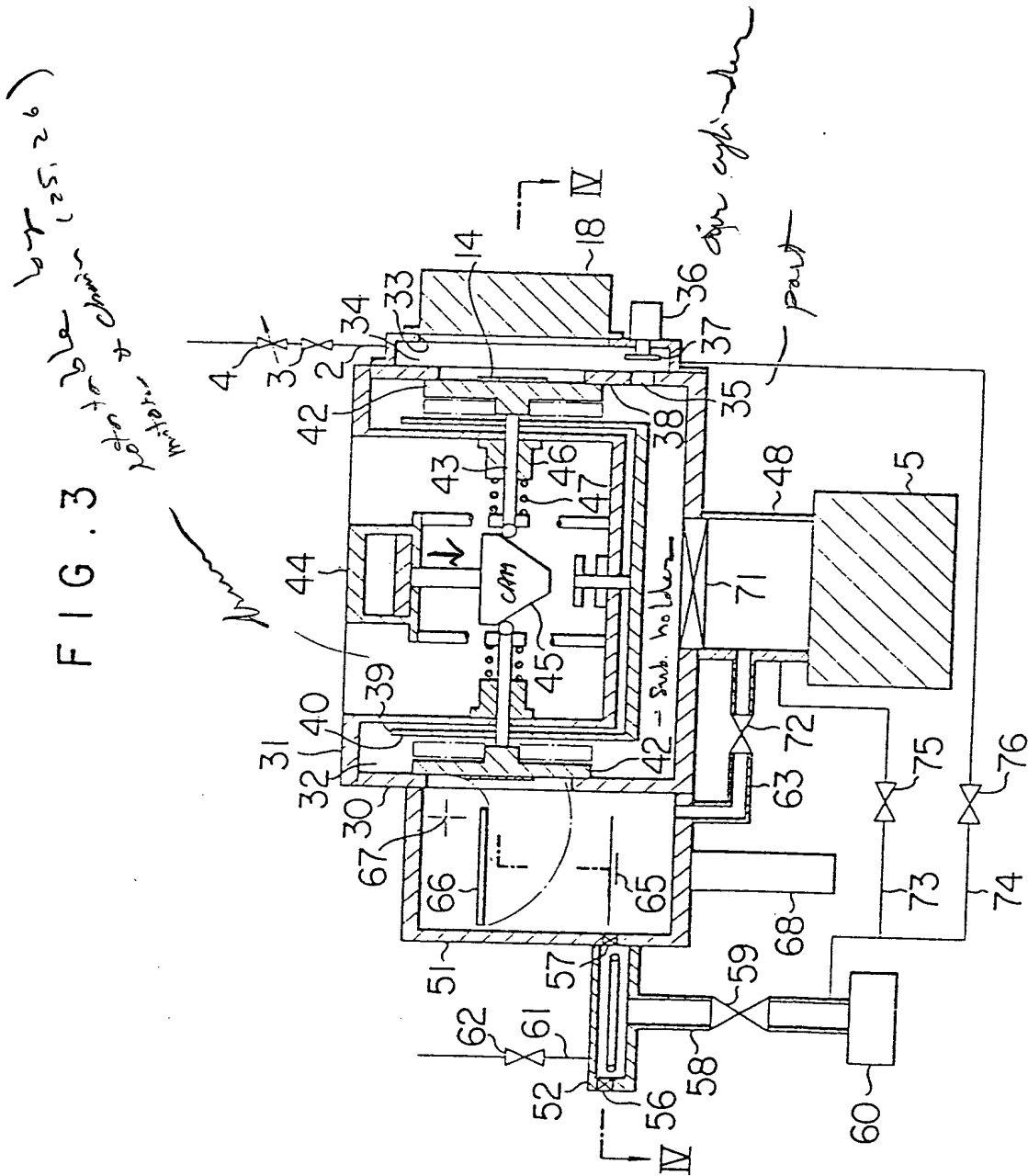
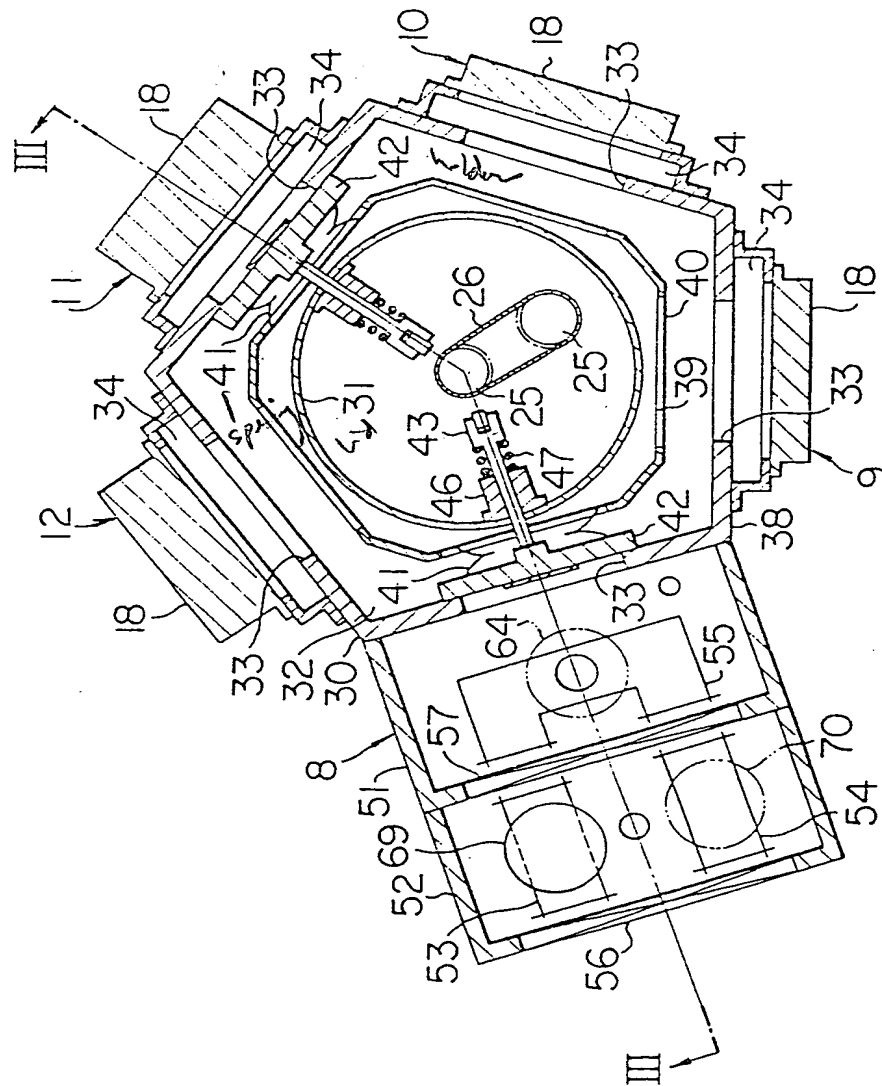


FIG. 4



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